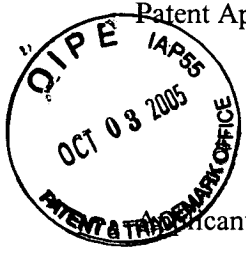


IFW



Patent Application 10/823,149

Docket No. TS01/195CC (24061.579)
Customer No. 42717

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant:	Lain-Jong Li, et al.	§	Docket No.:	TS01-195CC (24061.579)
Serial No.:	10/823,149	§	Examiner:	David Nhu
Filed:	April 13, 2004	§	Art Unit:	2818
For:	Composite Etching Step in	§	Conf. No.:	4561
	Semiconductor Process Integration	§		

RESPONSE TO RESTRICTION REQUIREMENT

Commissioner for Patents
Mail Stop: Amendment
PO Box 1450
Alexandria, VA 22313-1450

Dear Sir:

The present paper is being submitted in response to the Restriction Requirement Office Action dated September 12, 2005 in the above-identified application.

Election of Claims begins on page 2 of this paper.

Amendments to the Claims are reflected in the Listing of Claims which begins on page 3 of this paper.

Remarks begin on page 6 of this paper.

I. Election

In the Office Action mailed September 12, 2005, the Examiner alleges that the application contains claims directed to two inventions and, thus, required restriction of either:

Group I: Claim 1, drawn to a method of fabricating an integrated circuit device; or

Group II: Claims 27-46, drawn to an integrated circuit device.

In response, Applicants hereby elect Group II, corresponding to claims 27-46. Applicants' election is made with traverse on the grounds that the embodiments delineated by the Examiner are not patentably distinct and therefore constitute a single invention concept.